Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	235	tokyo.asn. and electron.asn. and (heat near4 chamber) and heater	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/15 11:49
L2	2	tokyo.asn. and electron.asn. and (recirculating) and (coating near10 solution)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/15 11:51
L3	1	tokyo.asn. and electron.asn. and (recirculation) and (coating near10 solution)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/15 11:51
L4	6	tokyo.asn. and electron.asn. and (recycling) and (coating near10 solution)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/15 11:51
L5	6	(("5168887") or ("5235995") or ("5431421") or ("5658387") or ("6066575") or ("6375741")).PN.	USPAT	OR	OFF	2004/11/15 11:54
L6	0	5 and (recircul)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/15 11:59
L7	2	5 and (recircul\$)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/15 11:54
L8	4	5 and framework	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2004/11/15 11:59

L9	5	5 and (processor near3 head)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/15 12:00
L10		5 and ("250")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2004/11/15 12:15
L11	0	5 and (dissipator)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/15 12:16
L12	0	5 and (dissipater)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/15 12:16
L13	0	5 and ((heat near4 source) same platform)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/15 12:16
L14	1	5 and ((heat near4 chamber))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/15 12:16

C1	40	LIC 2C41072 + DID 07		1 _		
S1	49	US-3641973-\$.DID. OR	US-PGPUB;	OR	ON	2004/11/14 20:49
ļ		US-3770598-\$.DID. OR	USPAT;			
		US-3798056-\$.DID. OR	USOCR;			
		US-3950184-\$.DID. OR	EPO; JPO;			•
		US-3962047-\$.DID. OR	DERWENT;			
		US-3978578-\$.DID. OR	IBM_TDB			
		US-4027686-\$.DID. OR				
		US-4092176-\$.DID. OR				
	-	US-4110176-\$.DID. OR				
		US-4113492-\$.DID. OR				
		US-4118303-\$.DID. OR				
		US-4137867-\$.DID. OR				
		US-4170959-\$.DID. OR				
		US-4226208-\$.DID. OR				
		US-4246088-\$.DID. OR				
		US-4259166-\$.DID. OR				
		US-4280882-\$.DID. OR				
		US-4304641-\$.DID. OR				
		US-4315059-\$.DID. OR				
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	İ	US-4339313-\$.DID. OR				
1		US-4339319-\$.DID. OR				
		US-4341613-\$.DID. OR				
		US-4351266-\$.DID. OR				
		US-4373988-\$.DID.				
S2	25	US-3641973-\$.DID. OR	USPAT;	OR	ON	2004/11/14 21:07
		US-3770598-\$.DID. OR	USOCR	• • •	0.1	200 1/11/14 21.07
		US-3798056-\$.DID. OR				
		US-3950184-\$.DID. OR				
		US-3962047-\$.DID. OR				
		US-3978578-\$.DID. OR				
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		US-4259166-\$.DID. OR				
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		US-4373988-\$.DID.				
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S3	27	US-4376685-\$.DID. OR US-4405416-\$.DID. OR US-4428815-\$.DID. OR US-4435266-\$.DID. OR US-4466864-\$.DID. OR US-4469566-\$.DID. OR US-4489740-\$.DID. OR US-4510176-\$.DID. OR US-4514266-\$.DID. OR US-4518678-\$.DID. OR US-4534832-\$.DID. OR US-4597836-\$.DID. OR US-4696729-\$.DID. OR US-4696729-\$.DID. OR US-4732785-\$.DID. OR US-4828654-\$.DID. OR US-4838979-\$.DID. OR	USPAT; USOCR	OR	ON	2004/11/14 21:37
54		US-4879007-\$.DID. OR US-4906346-\$.DID. OR US-4924890-\$.DID. OR US-4931149-\$.DID. OR US-5000827-\$.DID. OR US-5024746-\$.DID. OR US-5039381-\$.DID. OR US-5055425-\$.DID. OR US-5069760-\$.DID. OR US-5078852-\$.DID. OR US-5092975-\$.DID. OR US-5096550-\$.DID. OR US-5100502-\$.DID. OR US-5100516-\$.DID. OR US-5155336-\$.DID. OR US-5158100-\$.DID. OR US-5162260-\$.DID. OR US-5162260-\$.DID. OR US-5222310-\$.DID. OR US-5222310-\$.DID. OR US-5222310-\$.DID. OR US-5224504-\$.DID. OR US-5227041-\$.DID. OR US-5228966-\$.DID. OR US-5230743-\$.DID. OR US-5238500-\$.DID. OR US-5238500-\$.DID. OR	USPAT; USOCR	OR	ON	2004/11/14 21:14

S5	21	US-5290361-\$.DID. OR US-5294257-\$.DID. OR US-5312487-\$.DID. OR US-5316974-\$.DID. OR US-5328589-\$.DID. OR US-5232328-\$.DID. OR US-5332487-\$.DID. OR US-5235995-\$.DID. OR US-5252137-\$.DID. OR US-5270248-\$.DID. OR US-5340437-\$.DID. OR US-5349978-\$.DID. OR US-5377708-\$.DID. OR US-5377708-\$.DID. OR US-5391285-\$.DID. OR US-5405518-\$.DID. OR	USPAT; USOCR	OR	ON	2004/11/14 21:14
S6	2	US-5421987-\$.DID. OR US-5429733-\$.DID. ("4651640").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT;		OFF	2004/11/14 21:38
S7	2	("4651440").PN.	IBM_TDB US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT;	OR	OFF	2004/11/14 22:08
S8	2	("5156174").PN.	IBM_TDB US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 22:49
S9	2	("4590094").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/15 09:19
S10	10	("3136323" "3494815" "4027686" "4161356" "4745422" "4788994" "4871417" "4922277").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/11/14 22:28
S11	109	"118"/\$.ccls. and polyvinylidene and fluoride	US-PGPUB; USPAT; USOCR	OR	ON	2004/11/14 22:29

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S12	90	"118"/\$.ccls. and (polyvinylidene near2 fluoride)	US-PGPUB; USPAT; USOCR	OR	ON	2004/11/14 22:29
S13	1	"118"/\$.ccls. and (polyvinylidene near2 fluoride) and (acid near3 resistant)	US-PGPUB; USPAT; USOCR	OR	ON	2004/11/14 22:51
S14	9	"118"/\$.ccls. and (polyvinylidene near2 fluoride) and (wafer near3 holder)	US-PGPUB; USPAT; USOCR	OR	ON	2004/11/14 22:29
S15	0	"118"/\$.ccls. and (polyvinylidene near2 fluoride) and (wafer near3 chuck)	US-PGPUB; USPAT; USOCR	OR	ON	2004/11/14 22:30
S16	1	"118"/\$.ccls. and (polyvinylidene near2 fluoride) and (semiconductor same chuck)	US-PGPUB; USPAT; USOCR	OR	ON	2004/11/14 22:31
S17	10	"118"/\$.ccls. and (polyvinylidene near2 fluoride) and (semiconductor same holder)	US-PGPUB; USPAT; USOCR	OR	ON	2004/11/14 22:31
S18	6	(("5168887") or ("5235995") or ("5431421") or ("5658387") or ("6066575") or ("6375741")).PN.	USPAT	OR	OFF	2004/11/14 22:50
S19	44	semitool and polyvinylidene	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/14 22:51
S20	41	semitool.asn. and (polyvinylidene near2 fluoride)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/14 22:51
S21	12	(semiconductor or wafer) and (process\$5 near10 chamber) and (polyvinylidene near2 fluoride) and (acid near3 resistant)	US-PGPUB; USPAT; USOCR	OR	ON	2004/11/14 23:49
S22	1409	(118/52).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 22:51
S24	799	(118/302).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 22:52

S25	1656	(118/323).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 22:52
S26	88	(118/21).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 22:52
S27	143	(118/683).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 22:53
S28	287	(118/667).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 22:53
S29	1171	(118/300).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 22:53
S30	525	(118/313).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 22:53
S31	861	(118/315).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 22:53
S32	944	(118/320).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:28
S33	0	(semiconductor or wafer) and (process\$5 near10 chamber) and (polyvinylidene near2 fluoride) and (acid near3 retardant)	US-PGPUB; USPAT; USOCR	OR	ON	2004/11/14 22:56

C24	100-	(427/240) 6016			·T ·	
S34	1395	(427/240).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:29
S35	2456	(427/372.2).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:29
S36	811	(427/421).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:29
S37	0	(427/423).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:29
S38	567	(427/425).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:29
S39	152	(427/72).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:29
S40	1599	(427/96).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:29
S41	241	(438/760).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:29

S42	766	(438/758).CCLS.	US-PGPUB;	OR	OFF	2004/11/14 22:20
			USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB			2004/11/14 23:30
S44	510	(438/782).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:30
S45	766	(134/33).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:30
S46	351	(134/149).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:30
S47	1115	(134/153).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:30
548	638	(134/157).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:31
S49	2240	(134/902).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:31
S50	697	(134/182).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:31

S51	1050	(134/200).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:31
S52	429	(134/183).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/14 23:31
S53	9	(semiconductor or wafer) and ((process\$5 near10 chamber) same (acid near3 resistant))	US-PGPUB; USPAT; USOCR	OR	ON	2004/11/14 23:51
S54	2	(("4222345") or ("4282825")).PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/11/15 11:26